

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	9	MEMS and getter and cavity and cover and (substrate or wafer or semiconductor) and chamber and vacuum and "inert gas" and (temperature or heat or degree) and bond\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/29 12:28
S2	109	getter and cavity and cover and (substrate or wafer or semiconductor) and chamber and vacuum and "inert gas" and (temperature or heat or degree) and bond\$4	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/23 14:47
S3	1	getter and cavity and cover and (substrate or wafer or semiconductor) and chamber and vacuum and "inert gas" and (temperature or heat or degree) and bond\$4 and titanium and time and argon and discharg\$4 and anodic	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/23 14:48
S4	25	getter and cavity and cover and (substrate or wafer or semiconductor) and chamber and vacuum and "inert gas" and (temperature or heat or degree) and bond\$4 and titanium and time and argon	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/23 14:48
S5	144	adhes\$4 and conduct\$4 and binder and filler and (heat\$4 or thermal or temperature) and pressuriz\$4 and viscosity and connect and (hard\$4 or solid)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/03/29 12:32